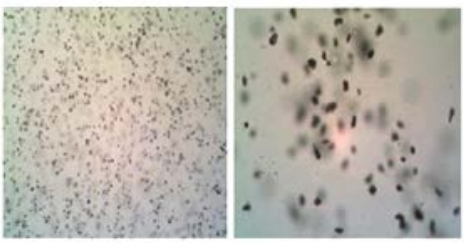
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Polishing slurry and Powder

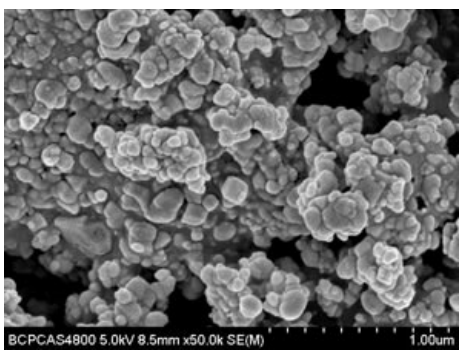
SUNTEK Polishing slurry is widely used for polishing and lapping opticas lense, quart plate, sapphire wafer, silicon wafer and fine ceramics. It is made by highest quality diamond grain, abrasives and rare earth oxide, with advantage of fast heat transfer, ease of clean.



Abrasives	Girt size/μm	Application
Monocrystalline Diamond	0, 1, 2, 3, 4, 8, 12, 20, 28, 36, 54	Silicon, sapphire and optic wafer
Polycrystalline Diamond	0, 1, 2, 3, 4, 8, 10, 12 16	
Cerium oxide	0, 1, 2, 3, 4, 8, 10, 12 16, 20	



SUNTEK provide a range of superpure polishing powder, including diamond, silicon carbide, silicon oxide, cerium oxide and alumina oxide.
It is used in optics, communications, display, semiconductor and data storage industry etc.



Features:
1) High removal rate for precision polishing.
2) Adjustable particle size distribution and particle shape, adapting to different kinds of polishing.
3) Easily dispersed in water and non-water solvent.

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